

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Jun Ito, et al.

Serial No.: 10/020,460

Group Art Unit: 2811

Filed: December 18, 2001

Examiner: S. Crane

Honorable Commissioner of Patents

Washington, D.C. 20231

Sir:

For:

identified application as follows:

GROUP III NITRIDE COMPOUND SEMICONDUCTOR DEVICE

## **IN THE CLAIMS:**

## Please amend the claims to read as follows:

- 1: (Amended) A semiconductor device comprising:
  - a substrate;
- an undercoat layer formed on said substrate and comprising a metal nitride; and a group III nitride compound semiconductor layer formed on said undercoat layer, and separated from said substrate by at least said undercoat layer.
- 2. (Amended) A semiconductor device according to claim 1, wherein said metal nitride directly contacts said group III nitride compound semiconductor layer.
- 4. (Amended) A semiconductor device according to claim 1, wherein said undercoat layer comprises at least one member selected from the group consisting of titanium nitride, zirconium nitride, hafnium nitride, tantalum nitride, and a nitride of a metal alloy.
- 5. (Amended) A semiconductor device according to claim 1, wherein said substrate comprises one member selected from the group consisting of sapphire, silicon carbide, gallium nitride, silicon, gallium phosphide, and gallium arsenide.